



# Far-infrared magneto-optical generalized ellipsometry determination of free-carrier parameters in semiconductor thin film structures

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M5.32

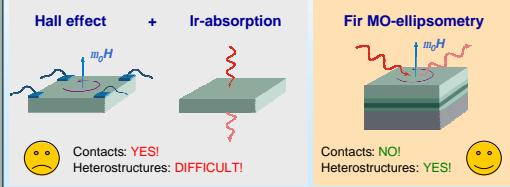
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## Our message

**New: far-infrared magneto-optic generalized ellipsometry:**  
Determination of the free-charge-carrier parameters effective electron mass, mobility, and concentration independent from each other by (far) infrared magneto-optic generalized ellipsometry.

How to determine free charge carrier parameters  
concentration, mass, and mobility in layered structures?

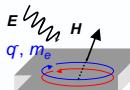


## Magneto-optical free-carrier effects

Free carrier movement in slowly time-dependent magnetic field  $H$

$$m_e^*\left(\frac{m_e}{q}\right)g + \partial_t v = \left[ E + \frac{H}{c}(v \times \mathbf{h}) \right]$$

Coulomb      Lorentz



$m_{e,h}^{*}$ : Free-carrier effective mass tensor  
 $\delta_{e,h}$ : Free-carrier scattering tensor (inverse relaxation time)  
 $q^+$ : Free-electron charge  
 $H$ : Magnetic field vector  $H = H(h_x, h_y, h_z)$   
 $E$ : Electric field vector of the incident light

### DF tensor

$$\mathbf{e}^{(FC-MO)}(\mathbf{w}, H) = -\left\langle \mathbf{w}_p^{i=2} \right\rangle \left[ (\mathbf{w}^2 I + iwg) - i\langle \mathbf{w}_p \rangle \begin{pmatrix} 0 & -h_3 & h_2 \\ h_3 & 0 & -h_1 \\ -h_2 & h_1 & 0 \end{pmatrix} \right]^{-1}$$

$$\text{Plasma (frequency) tensor } \langle \mathbf{w}_p^{i=2} \rangle \equiv N \frac{\mathbf{e}^2}{m_e} \mathbf{m}^3$$

$$\text{Cyclotron (frequency) tensor } \langle \mathbf{w}_c \rangle \equiv q \left( \frac{H}{m_e} \right) \mathbf{m}^{-1}$$

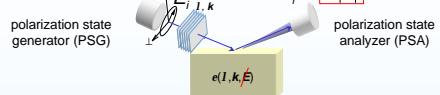
$H$  causes non-symmetric properties of the dielectric function tensor!

Magneto-optic tensor for  $B = \mu_0(0,0,H)$  (Faraday Configuration)

$$\mathbf{e}^{(FC-MO)}(\mathbf{w}) = \begin{pmatrix} e_{xx} & ie_{xy} & 0 \\ -ie_{xy} & e_{yy} & 0 \\ 0 & 0 & e_{zz} \end{pmatrix}$$

$$e_{xx}(\mathbf{w}) = -w_p^{-2} \frac{1}{w(w+ig_p)} \quad e_{yy}(\mathbf{w}) = -w_p^{-2} \frac{w_c}{w((w+ig_p)^2 - w_c^2)} \quad e_{zz}(\mathbf{w}) = -w_p^{-2} \frac{w + ig_p}{w((w+ig_p)^2 - w_c^2)}$$

## Experimental setup



## Model-dielectric function

Polar lattice contribution

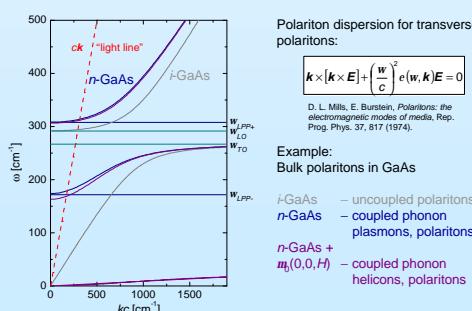
$$e_j(\mathbf{w}) = e_{-j} \prod_{i=1}^I \frac{w^2 + ig_{LO,i}w - w_{LO,i}^2}{w^2 + ig_{TO,i}w - w_{TO,i}^2} \prod_{k=1}^M \left( 1 + \frac{idg_{kj}w - dw_{kj}^2}{w^2 + ig_{AM,k}w - w_{AM,k}^2} \right) - e^{(FC-MO)}(\mathbf{w}, H)$$

Infrared-active phonon modes:  
 $\omega_{TO,0}$  – TO/LO phonon mode frequency  
 $\gamma_{TO,0}$  – TO/LO broadening parameter

Free-carrier contribution:  
 $w_{pj} \propto z_j = (Nm)^{0.5}$  – plasma frequency  
 $g_{pj} \propto x_j = (m_j \mu_j)^{-1}$  – scattering tensor  
 $N$  – free-carrier concentration  
 $m_j$  – free-carrier effective mass tensor  
 $\mu_j$  – free-carrier mobility tensor

$$e^{(FC-MO)}(\mathbf{w}, H=0) = \frac{w_p^2 e_{-j}}{w(w+ig_p)}$$

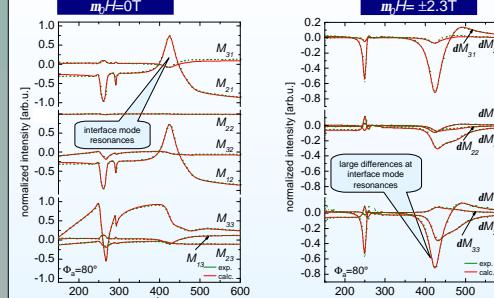
## Bulk Polaritons



## Example 1: n-GaAs-i-GaAs

GaAs-buffer ~ 700nm  
(001) GaAs  
un-doped GaAs-buffer layer  
n-type (Te doped) GaAs substrate

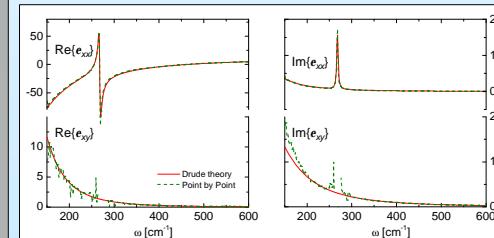
### Fir-mo generalized ellipsometry



The differences of the Mueller matrix elements normalized to  $M_{11}$ . Dominant structures originate from the excitation of interface modes. The GaAs TO and LO phonon mode can be recognized at  $\sim 268$  and  $\sim 291$  cm $^{-1}$ .

### Fir dielectric tensor

First measurement of the complex fir magneto-optic Drude Tensor!



Excellent agreement of the model and the point by point data. The  $e_{zz}$  spectra are virtually identical to the  $e_{xx}$  spectra and therefore omitted here.

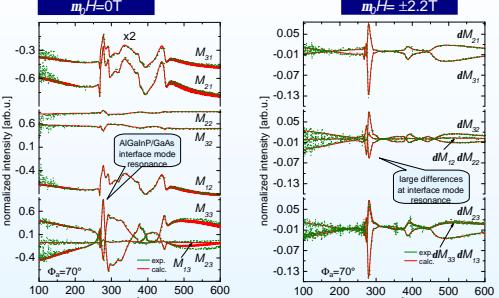
$m^* = 0.072 m_e$   
 $N = 1.6 \times 10^{18} \text{ cm}^{-3}$   
 $m = 2200 \text{ cm}^2/(Vs)$

Very good agreement of the effective electron mass at  $N = 1.6 \times 10^{18} \text{ cm}^{-3}$  with Shubnikov de Haas measurements and  $k \cdot p$  calculations.

## Example 2: n-GaAs/n-AlGaInP/i-GaAs

GaAs-cap ~ 70 nm  
Al<sub>0.19</sub>Ga<sub>0.33</sub>In<sub>0.48</sub>P  
GaAs-buffer ~ 20 nm  
(001) GaAs  
n-type (Te-doped) GaAs-cap  
n-type (Te-doped) Al<sub>0.19</sub>Ga<sub>0.33</sub>In<sub>0.48</sub>P epilayer  
undoped GaAs buffer and substrate

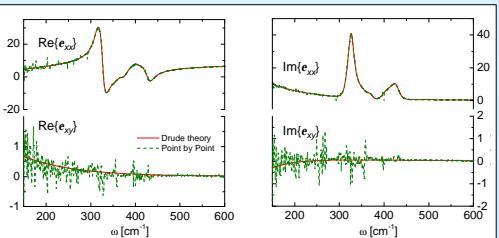
### Fir-mo generalized ellipsometry



The differences of the Mueller matrix elements normalized to  $M_{11}$ . Most of the structures are due to the excitation AlP-, InP-, or GaP-like phonon modes (see M5.33 also).

### Fir dielectric tensor

First effective mass determination for highly disordered AlGaInP!



Excellent agreement of the model and the point by point data. The  $e_{zz}$  spectra are virtually identical to the  $e_{xx}$  spectra and therefore omitted here.

$m^* = 0.12 m_e$   
 $N = 6.7 \times 10^{17} \text{ cm}^{-3}$   
 $m = 339 \text{ cm}^2/(Vs)$

New Data: First measurement of  $m^*$  in highly disordered AlGaInP. Good agreement with  $k \cdot p$  calculations.